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|---|-------|---|---|---------------------|
| - | 206 | (((((trench or trenches) and (epi or epitaxial)) and (mask or masking)) and (protrude or protruding or protruded)) and silicon | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB | 2002/02/01 14:28 |
| - | 0 | (((((trench or trenches) and (epi or epitaxial)) and (mask or masking)) and (protrude or protruding or protruded)) and silicon) and ((selective adj epi adj growth) or (blanket adj epi adj growth)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB | 2002/02/01 14:29 |
| - | 3 | (((((trench or trenches) and (epi or epitaxial)) and (mask or masking)) and (protrude or protruding or protruded)) and silicon) and (SEG or BEG) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB | 2002/02/01 14:31 |
| - | 315 | ((trench or trenches) and (epi or epitaxial)) and (mask or masking)) and silicon and ((selective adj epitaxial adj growth) or (blanket adj epitaxial adj growth)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB | 2002/02/01 14:32 |
| - | 311 | (((((trench or trenches) and (epi or epitaxial)) and (mask or masking)) and silicon and ((selective adj epitaxial adj growth) or (blanket adj epitaxial adj growth)) and substrate | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB | 2002/02/01 14:33 |
| - | 311 | (((((trench or trenches) and (epi or epitaxial)) and (mask or masking)) and silicon and ((selective adj epitaxial adj growth) or (blanket adj epitaxial adj growth)) and substrate) and (remove or removal or removing or removed or etch or etching or etched) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB | 2002/02/01 14:34 |
| - | 31 | (((((trench or trenches) and (epi or epitaxial)) and (mask or masking)) and silicon and ((selective adj epitaxial adj growth) or (blanket adj epitaxial adj growth)) and substrate) and (remove or removal or removing or removed or etch or etching or etched)) and (trench near3 (align or aligned or alignment or aligning)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB | 2002/02/04 13:37 |
| - | 48 | (438/245, 270, "259").ccls. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB | 2002/02/01 15:08 |
| - | 0 | 438/245.ccls | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB | 2002/02/01 15:08 |
| - | 1391 | 438/270.ccls. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB | 2002/02/01 15:09 |
| - | 48 | 438/245.ccls. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB | 2002/02/01 15:09 |
| - | 193 | 438/259.ccls. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB | 2002/02/01 15:47 |
| - | 15107 | (trench or trenches) and (mask or masking) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB | 2002/02/01 15:47 |